

What Is Claimed Is:

1. A color filter substrate for a liquid crystal display device, comprising:
 - a substrate;
 - a black matrix having a plurality of open portions on the substrate;
 - a color filter layer on the black matrix; and
 - a dielectric layer including first and second layers on the color filter layer, wherein the first layer has a uniform thickness and the second layer has a convex pattern, and the first and second layers include the same material.
2. The substrate according to claim 1, wherein the color filter layer includes red, green, and blue sub-color filters.
3. The substrate according to claim 2, wherein one of the plurality of sub-color filters corresponds to one of the plurality of open portions.
4. The substrate according to claim 1, wherein the convex pattern corresponds to the black matrix.

5. The substrate according to claim 1, wherein the first layer planarizes the color filter layer and the second layer maintains a cell gap of the liquid crystal display device.

6. A method of fabricating a color filter substrate for a liquid crystal display device, comprising:

forming a black matrix having a plurality of open portions on a substrate;

forming a color filter layer on the black matrix;

forming an overcoat layer on the color filter layer;

forming a positive-type photoresist layer on the overcoat layer;

forming a photoresist pattern corresponding to the black matrix using photolithographic processes of the photoresist layer; and

etching the photoresist pattern and the overcoat layer to form a dielectric layer.

7. The method according to claim 6, wherein the photoresist and the overcoat layer are etched using a dry etching method.

8. The method according to claim 6, wherein the overcoat layer includes an acrylic material.

9. The method according to claim 6, wherein the dielectric layer includes a first layer having a uniform thickness and a second layer having a convex pattern corresponding to the black matrix.

10. The method according to claim 9, wherein the first layer planarizes the color filter layer and the second layer maintains a cell gap of the liquid crystal display device.

11. The method according to claim 6, wherein forming the photoresist pattern comprises:

disposing a photo mask having a transmissive portion and a shielding portion over the photoresist layer, the transmissive portion and the shielding portion corresponding to the plurality of open portions and the black matrix;

exposing the photoresist layer using the photo mask; and

developing the photoresist layer.

12. The method according to claim 6, wherein the photoresist pattern and the overcoat layer have substantially the same etching rate.

13. The method according to claim 12, wherein a thickness of the photoresist pattern is substantially the same as a thickness of the second layer of the dielectric layer.

14. The method according to claim 6, wherein the photoresist pattern is transcribed onto the overcoat layer.

15. A liquid crystal display device, comprising:

first and second substrates;

a thin film transistor, a common electrode, and a pixel electrode on the first substrate;

a black matrix having a plurality of open portions on the second substrate;

a color filter layer on the black matrix;

a dielectric layer including first and second layers on the color filter layer;

and

a liquid crystal layer between the first and second substrates,

wherein the first layer has a uniform thickness and the second layer has a convex pattern, and the first and second layers include the same material.

16. The device according to claim 15, wherein the first layer planarizes the color filter layer and the second layer maintains a cell gap defined by a thickness of the liquid crystal layer.

17. A method of fabricating a liquid crystal display device, comprising:

forming a thin film transistor, a common electrode, and a pixel electrode on a first substrate having a plurality of sub-pixel regions;

forming a black matrix having a plurality of open portions corresponding to the sub-pixel region on a second substrate;

forming a color filter layer on the black matrix;

forming an overcoat layer on the color filter layer;

forming a photoresist layer on the overcoat layer;

forming a photoresist pattern corresponding to the black matrix using the photoresist layer;

etching the photoresist pattern and the overcoat layer to form a dielectric layer;

attaching the first and second substrates; and

forming a liquid crystal layer between the first and second substrates.

18. The method according to claim 17, wherein the dielectric layer includes a first layer having a uniform thickness and a second layer having a convex pattern corresponding to the black matrix.

19. The method according to claim 18, wherein the first layer planarizes the color filter layer and the second layer maintains a cell gap of the liquid crystal display device.

20. The method according to claim 19, wherein a thickness of the second layer is substantially the same as a thickness of the liquid crystal layer.